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10/24/03
(Date of Deposit)

Karen Cinq-Mars
(Signature)

10/24/03
(Date)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of : October 23, 2003
Huang et al. :
Serial No. : Examiner:
Filed: Herewith : IBM Corporation
Dept. 18G/Bldg. 300-482
2070 Route 52
Hopewell Junction,
New York 12533-6531
Title: LOW-ACTIVATION ENERGY
SILICON-CONTAINING RESIST
SYSTEM :

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

In compliance with the duty of disclosure under
37 C.F.R. § 1.56 and in accordance with the practice under
37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to
the documents listed on the enclosed Form PTO-1449. Copies of the
listed documents are also enclosed, excluding US patents.

It is respectfully requested that the above information be
considered by the Examiner and that a copy of the enclosed Form
PTO-1449 be returned indicating that such information has been
considered.

Applicants undersigned attorney may be reached by telephone

FIS920030330

at (845) 894-6919. All correspondence should continue to be directed to the below listed address.

Respectfully submitted,

 10/23/03

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INTERNATIONAL BUSINESS MACHINES CORPORATION
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TML/kcm

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>	ATTY DOCKET NO. FIS920030330US1	SERIAL NO.
	Huang et al.	
	FILING	GROUP

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		2002/0081520	06-27-02	Sooriyakumaran et al.			
		2001/0036594	11-01-01	Kozawa et al.			
		6,531,260	03-11-03	Iwasawa et al.			
		6,420,088	07-16-02	Angelopoulos et al.			
		6,623,909	09-23-03	Hatakeyama et al.			
		2003/0113658	06-19-03	Ebata et al.			
		6,043,003	03-28-00	Bucchignano et al.			
		6,037,097	03-14-00	Bucchignano et al.			
		5,712,078	01-27-98	Huang et al.			
		6,087,064	07-11-00	Lin et al.			
		2002/0090572	07-11-02	Sooriyakumaran et al.			

FOREIGN PATENT DOCUMENTS								
*		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS	(Including Author, Title, Date, Pertinent Pages, Etc.)
	"Effects of resist components on image spreading during postexposure bake of chemically amplified resists", Hinsberg et al. Proceedings of SPIE Vol. 3999 (2000), ppgs. 148-160 "Determination of coupled acid catalysis-diffusion processes in a positive-tone chemically amplified photoresist" Houle et al. Journal Vac. Sci. Technology B 18 (4) Jul/Aug 2000, ppgs. 1874-1885
	"Direct measurement of the reaction front in chemically amplified photoresists" Lin et al. Science, Vol. 297, 19 July 2002, ppgs. 372-375 "Modeling and simulations of a positive chemically amplified photoresist or ex-ray lithography", Krasnoperova et al., Journal Vac. Sci. Technology B 12 (6) Nov/Dec 1994, ppgs. 3900-3904

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Huang et al.

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U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5,985,524	11-16-99	Allen et al.			
	2002/0058204	05-16-02	Khojasteh et al.			
	2003/0073040	04-17-03	Iwasawa et al.			
	6,420,084	07-16-02	Angelopoulos et al.			

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	0 628 876 A1	05-25-94	EPO				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Appl. no. 10/241,937, FIS9-2002-0057US1 "Low silicon-outgassing resist for bilayer lithography" Kwong et al. Filed 9-11-02
	Appl. no. 10/604,082, FIS9-2003-0159US1 "Process for forming features of 50 nm or less half-pitch with chemically amplified resist imaging" Medeiros et al., Filed 06-25-03
	Appl. no. 10/026,184, FIS9-2001-0380US1 "Underlayer compositions for multilayer lithographic processes", Khojasteh et al., Filed 12-21-01
	Appl. No. 10/079,289, YOR9-2000-0693US2, "Substantially transparent aqueous base soluble polymer system for use in 157 nm resist applications" Sooriyakumaran et al., Filed 02-20-02

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